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			Sileet 1 Of 1			
			ATTY DOCKET NO.	SERIAL NO.		
INFORMATION DISCLOSURE STATEMENT			536-009.027	To be assigned		
			APPLICANT: Holger RUCKER et al.			
			FILING DATE:	ART UNIT:		
			Herewith	To be assigned		
		UNITED STA	TES PATENT DOCUMENT	s		
	DOCUMENT NUMBER	DATE	INVENTOR/ASSIGNEE	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
US	2002/0117733	Aug. 29, 2002	Michael Farjami, Esq.			
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US	6,642,553	Nov. 4, 2003	Juergen Drews et al.			
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ΕP	0 418 185 A1	Jul. 31, 1990	EP			
ΕP	1 128 422 A1	Aug. 29, 2001	EP			
EΡ	0 949 665 A2	Apr. 7, 1999	EP			
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	H.J. Osten et al., The Effect of Carbon Incorporation on SiGe Heterobipolar Transistor Performance and Process Margin; IEEE 1997 0-7803-4100 (pages 32.4.1 - 32.4.4).					
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